PALM INTRANET

Day : Thursday
Date: 4/15/2004
Time: 08:59:41

Inventor Name Search Result

Your Search was:

Last Name = TAKAHASHI
First Name = HIROKO

Application#	Patent#	Status	Date Filed	Title	Inventor Name 8
10670515	Not Issued	030	09/26/2003	PROCESS FOR PRODUCING NORBORNENE DERIVATIVE HAVING ORGANOSILYL GROUP	TAKAHASHI, HIROKO
10331283	Not Issued	030	12/30/2002	MONITORING DEVICE AND MONITORING SYSTEM FOR MONITORING THE LOCATION OF COMMUNICATION DEVICES	TAKAHASHI, HIROKO
09949690	Not Issued	030	09/10/2001	NETWORK MANAGEMENT METHOD AND APPARATUS	TAKAHASHI, HIROKO
09474167	Not Issued	093	12/29/1999	NODE EQUIPMENT, TERMINAL EQUIPMENT, AND STORAGE MEDIUM WHICH STORES PROGRAM FOR REALIZING THESE EQUIPMENTS	TAKAHASHI, HIROKO
09337521	6294703	150	06/22/1999	PROCESS FOR THE MANUFACTURE OF CYCLOALKYLDIMETHANOL	TAKAHASHI , HIROKO
09322633	6232411	150	05/28/1999	HYDROGENATED DIGYLCIDYL ETHERS OF BIPHENY-4,4'-DIOL	TAKAHASHI , HIROKO
09199779	6130344	150	11/25/1998	PROCESS FOR PRODUCING COMPOUND HAVING EPOXY GROUP	TAKAHASHI , HIROKO
08734789	6014649	150	10/22/1996	ATM OPERATION SUPPORTING SYSTEM	TAKAHASHI , HIROKO

Inventor Search Completed: No Records to Display.

Search Another: Inventor **Last Name** TAKAHASHI **First Name** HIROKO Search

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(FILE 'HOME' ENTERED AT 08:59:50 ON 15 APR 2004)

FILE 'REGISTRY' ENTERED AT 09:00:01 ON 15 APR 2004

FILE 'CAPLUS' ENTERED AT 09:00:31 ON 15 APR 2004
E TAKAHASHI HIROKO/AU
L1 95 S E3
L2 13881 S NORBORNENE
L3 2 S L2 AND L1

=> d bib abs 1-2

L3 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2004 ACS on STN
AN 2004:269918 CAPLUS
TI Process for producing **norbornene** derivative having organosilyl group
IN **Takahashi, Hiroko**; Takahashi, Takako; Naito, Taketoshi; Ichikawa, Shuji
PA Mitsubishi Chemical Corporation, Japan
SO U.S. Pat. Appl. Publ., 5 pp.
CODEN: USXXCO
DT Patent
LA English
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2004063982	A1	20040401	US 2003-670515	20030926
PRAI JP 2002-286353	A	20020930		
JP 2003-150810	A	20030528		

AB A process for producing a **norbornene** derivative having an organosilyl group suitable as a synthetic intermediate for pesticides and medicaments and for production of polyolefin polymers, particularly polyolefin polymers having a good adhesiveness with metals or insulating inorg. materials in high yields with a satisfactory purity. A process for producing a **norbornene** derivative having an organosilyl group I (SiZ = SiRnR13-n; R = alkyl, aryl, R1 = alkyl, aryl; n = 0-2; m = 0 or more), which comprises reacting I (SiZ = SinRnX3-n; R, n, m = same as above; X = halo), with a Grignard reagent R1MgCl (R1 = same as above). Thus, reaction of vinyltrichlorosilane with cyclopentadiene at 70° for 3h gave 75% trichlorosilylnorbornene which on treatment with MeMgCl in THF gave 92% trimethylsilylnorbornene.

L3 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2004 ACS on STN
AN 2003:391026 CAPLUS
DN 138:385294
TI Method for preparation of **norbornene** lactones
IN Okago, Yuji; **Takahashi, Hiroko**; Takahashi, Takako; Naito, Taketoshi
PA Mitsubishi Chemical Corp., Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003146979	A2	20030521	JP 2001-349159	20011114
PRAI JP 2001-349159		20011114		

OS CASREACT 138:385294; MARPAT 138:385294
GI

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

AB Norbornenedicarboxylic acid anhydride-derived lactones [I, II, III, and IV; R1-R8 = H, (un)substituted C1-8 linear or branched or alicyclic alkyl] are prepared by reduction of norbornenedicarboxylic acid anhydrides (V, VI; R1-R8 = same as above) with a reducing agent, in particular alkali metal borohydride, in the presence of a primary or secondary alc. in high yields under mild conditions. The lactones further undergo addition reaction to the double bond with (meth)acrylic acid to give (meth)acrylic acid esters. The lactones are useful as raw materials for drugs and agrochems. and lactone (meth)acrylic acid esters are useful as monomers for resist materials with excellent sensitivity, resolution, and etching resistance in microprocessing using electron beam and UV rays (no data). Thus, a solution of 15.38 g MeOH and 78.80 g 5-**norbornene**-2,3-dicarboxylic acid anhydride in 250 mL THF to a mixture of 18.15 g NaBH4 and 350 mL THF at ≤8° under cooling in an ice-salt bath over 1 h, followed by carefully adding 280 mL aqueous HCl to give, after workup, 3-oxo-4-oxatricyclo[5.2.1.02'6]dec-8-ene, i.e. I (R1-R8 = H). I (R1-R8 = H) (13.12 g) and 30 mg 4-methoxyphenol were dissolved in 30.09 g methacrylic acid, treated with 3.62 g 95% H2SO4, stirred at 120° for 3 h, cooled to room temperature, carefully poured into a solution of 4 g Na2CO3 in 100 mL H2O, extracted with 100 mL toluene to give, after further workup, 76% 3-oxo-4-oxatricyclo[5.2.1.02'6]decan-8-yl methacrylate.

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